



Office – (512) 971-1531
 Fax – (512) 312-5977
 Email - SSIParts@austin.rr.com

ALS-1713

Printable Data Page

ALS-1713 System Configuration

Lens	G-Line, Zeiss 10-78-46 .38na
AWHIII	Automatic Wafer Handler configured to cycle 25 6” wafers. May be configured for 3” to 8” wafers. 1”, 2”, or single chips may be loaded by hand.
Thetalll	Automatically levels wafers. Chuck maybe tilted with software corrections to optimize field flatness.
RMS10	Ten 5” reticles made be loaded and stored.
Maxi 2000	G line light source uses 1000W lamps.
AFS 100	Automatic Focusing system.
DFAS	Local alignment system measures and corrects stage alignment prior to stepping.
SmartSet	Metrology computer system used to process and store data necessary to match single or multiple steppers.
Insitu	Probe mounted to stage and used to measure and correct for lens reduction, rotation, and focus. It also measures and corrects system alignment baselines.
IQ Probe	Probe used to optimize lamp position and light source uniformity. It also accurately measures and corrects Dose.
PPCII	Programmable platen control automatically adjusts reticle load position without the need for hardware adjustments.
IAS	Integrated Alignment System performs digital alignment of global targets.
Chamber	8860 environmental chamber protects the stepper while maintaining temperature and cleanliness.

ALS-1713 Specifications

System Resolution	0.9um Line/Space
Depth of Focus	1.5um
Illumination Uniformity	±2.5%

Illumination Intensity	>300mw/cm²
Open Frame	No Repeaters
Reduction	±0.1um
Rotation	≤0.05um
Telecentricity	≤1.5ppm/um
Stepping Repeatability	≤0.15um
Global Alignment	±0.25um
Local Alignment	±0.15um
RMS Reliability	100 Cycles
Reticle Blade Accuracy	±0.25mm
AWH Reliability	100 Wafers
AWH Accuracy	±0.003”
Leveling Repeatability	±5ppm from nominal

Please Call for Details (Pricing, Installation, Warranty).